



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application

SC/Serial No.: SEE SCHEDULE A  
Filed: SEE SCHEDULE A  
Title: SEE SCHEDULE A

PATENT APPLICATION

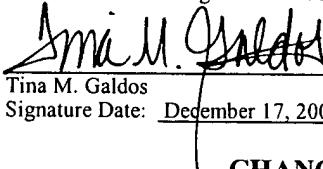
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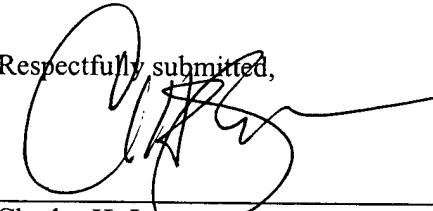
Sir:

I am the attorney of record for the patents and patent applications listed on Schedule A attached hereto. Please be notified that my address has changed to the following:

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Please send all future correspondence concerning the patent and patent applications listed on Schedule A to the above address.

Date: 12-17-02

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Respectfully submitted,

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**SCHEDULE A****LIST OF ISSUED PATENTS**

| Title  | Filing Date | U.S. Serial No. | Issue Date | Patent No. | Old (BDSM) Attorney Docket No. | New Attorney Docket No. |
|--|-------------|-----------------|------------|------------|--------------------------------|-------------------------|
| Null Test Fourier Domain Alignment Technique for Phase-Shifting Point Diffraction Interferometer | 1/12/1999   | 09/229,449      | 8/29/2000  | 6,111,646  | 015780-024                     | LBLL-01024US0           |
| Phase-Shifting Point Diffraction Interferometer Mask Designs                                     | 10/21/1998  | 09/176,617      | 10/23/2001 | 6,307,635  | 015780-025                     | LBLL-01025US0           |
| Phase-Shifting Point Diffraction Interferometer Grating Designs                                  | 10/21/1998  | 09/176,695      | 2/27/2001  | 6,195,169  | 015780-027                     | LBLL-01027US0           |
| Phase-Shifting Point Diffraction Interferometer Focus-Aid Enhanced Mask                          | 7/26/1999   | 09/361,780      | 11/21/2000 | 6,151,115  | 015780-028                     | LBLL-01028US0           |
| Dual-Domain Point Diffraction Interferometer   | 4/27/1999   | 09/300,539      | 8/8/2000   | 6,100,978  | 015780-030                     | LBLL-01030US0           |
| In Situ Alignment System for Phase Shifting Point-diffraction Interferometry                     | 6/2/1999    | 09/324,903      | 9/12/2000  | 6,118,535  | 015780-031                     | LBLL-01031US0           |
| Phase-Shifting Point Diffraction Interferometer Phase Grating Designs                            | 10/14/1999  | 09/419,703      | 7/24/2001  | 6,266,147  | 015780-032                     | LBLL-01032US0           |
| Interferometric Al-Wavelength Flare Characterization of EUV Optical System                       | 7/28/2000   | 09/627,533      | 5/15/2001  | 6,233,056  | 015780-033                     | LBLL-01033US0           |
| Method of Fabricating Reflection-Mode EUV-Diffraction Elements                                   | 12/5/2000   | 09/730,970      | 5/21/2002  | 6,392,792  | 015780-039                     | LBLL-01039US0           |

**SCHEDULE A****LIST OF PENDING PATENT APPLICATIONS**

| Title  | Filing Date | U.S. Serial No. | Old (BDSM) Attorney Docket No. | New (FDML) Attorney Docket No. |
|--|-------------|-----------------|--------------------------------|--------------------------------|
| Method and Apparatus for Inspecting Reflection Masks for Defects               | 11/17/1998  | 09/193,198      | 015780-026                     | LBLL-01026US0                  |
| System for Interferometric Distortion Measurements That Define an Optical Path | 5/11/2000   | 09/569,168      | 015780-029                     | LBLL-01029US0                  |
| Dual-Domain Lateral Shearing Interferometer                                    | 8/4/2000    | 09/632,631      | 015780-034                     | LBLL-01034US0                  |
| Hybrid Shearing and Phase-Shifting Point Diffraction Interferometer            | 7/17/2000   | 09/617,719      | 015780-035                     | LBLL-01035US0                  |
| Method of Fabricating Reflection-Mode EUV Diffusers                            | 4/30/2001   | 09/846,150      | 015780-040                     | LBLL-01040US0                  |
| Apparatus for Generating Partially Coherent Radiation                          | 8/30/2001   | 09/944,391      | 015780-041                     | LBLL-01041US0                  |
| A Holographic Illuminator for Synchrotron-Based Projection Lithography Systems | 10/16/2001  | 09/981,500      | 015780-042                     | LBLL-01042US0                  |
| Synchrotron-Based EUV Lithography Illuminator Simulator                        | 6/5/2002    | 10/163,479      | 015780-043                     | LBLL-01043US0                  |
| Diffractive Optical Element for Extreme Ultraviolet Wavefront Control          | 9/17/2001   | 09/956,160      | 015780-044                     | LBLL-01044US0                  |